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- (71) Applicant (for all designated States except US):  
**MALLINCKRODT BAKER INC.** [US/US]; 675  
McDonnell Boulevard, P.O. Box 5840, St. Louis, MO  
63134 (US).
- (72) Inventor; and
- (75) Inventor/Applicant (for US only): **SKEE, David, C.**  
[US/US]; 3192 Rambeau Road, Bethlehem, PA 18020  
(US).
- (74) Agents: **REBMAN, Christine, M.** et al.; Mallinckrodt  
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(54) Title: ALKALINE, POST PLASMA ETCH/ASH RESIDUE REMOVERS AND PHOTORESIST STRIPPING COMPOSITIONS CONTAINING METAL-HALIDE CORROSION INHIBITORS

(57) Abstract: The invention provides alkaline compositions useful in the microelectronics industry for stripping or cleaning semiconductor wafer substrates by removing photoresist residues and other unwanted contaminants. The compositions contain (a) one or more bases and (b) one or more metal corrosion inhibiting metal halides of the formula:  $W_zMX_y$ , where M is a metal selected from the group Si, Ge, Sn, Pt, P, B, Au, Ir, Os, Cr, Ti, Zr, Rh, Ru, and Sb; X is a halide selected from F, Cl, Br and I; W is selected from H, to an alkali or alkaline earth metal, and a metal ion-free hydroxide base moiety; y is a numeral of from 4 to 6 depending on the metal halide; and z is a numeral of 1, 2 or 3.

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